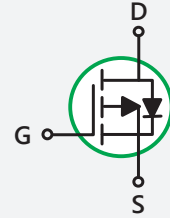
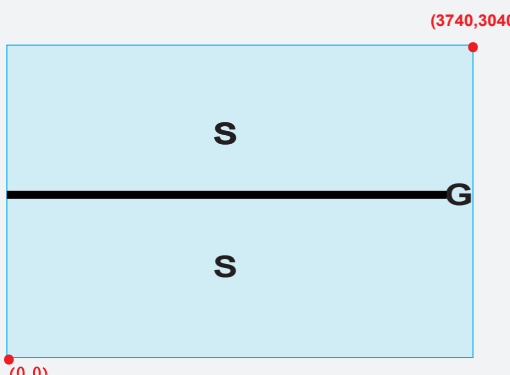


### -150V P Channel Enhancement MOSFET Wafer Datasheet

#### FEATURES

- P-Channel,-150V
- $R_{ds(ON)} = 52m\Omega$  (Typ.)@ $V_{GS} = -10V$
- Exceptional on-resistance and maximum DC current capability  
high density cell design for extremely low  $R_{DS(ON)}$



Bonding Pad Information	Chip Information		
	Wafer Name	DC6M150P052M7	
	Wafer Diameter	6 inches	
	Wafer Thickness	7 mils	
	Front-side Metallization	Al/Si/Cu (4um)	
	Back-side Metallization	Ti/Ni/Ag	
	Bonding Type	Gate: 1.5mil Cu x 1	
		Source: 40x6mil Al Ribbon x 2	
	Die Size (without scribe line)	3740um x 3040um	
	Scribe Line Width	60um	
	Gate Pad Size	340um x 460um	
Gross Die	1296 ea		

#### ABSOLUTE MAXIMUM RATINGS ( $T_c = 25^\circ C$ unless otherwise noted)

Parameter	Symbol	Limit	Units
Drain-Source Voltage	$V_{DS}$	-150	V
Gate-Source Voltage	$V_{GS}$	$\pm 20$	V
Operating Junction and Storage Temperature Range	$T_J, T_{STG}$	-55 to 150	$^\circ C$

#### ELECTRICAL CHARACTERISTICS ( $T_c = 25^\circ C$ unless otherwise noted)

Parameter	Symbol	Test Conditions	Min	Typ	Max	Units
Drain-Source Breakdown Voltage	$BV_{DSS}$	$V_{GS} = 0V, I_D = -250\mu A$	-150			V
Zero Gate Voltage Drain Current	$I_{DSS}$	$V_{DS} = -120V, V_{GS} = 0V$			-1	$\mu A$
Gate-Body Leakage Current	$I_{GSS}$	$V_{GS} = \pm 20V, V_{DS} = 0V$			$\pm 100$	nA
Gate Threshold Voltage	$V_{GS(th)}$	$V_{DS} = V_{GS}, I_D = -250\mu A$	-2	-3	-4	V
Drain-Source On-State Resistance	$R_{DS(ON)}$	$V_{GS} = -10V, I_D = -1A$		52	64	m ohm

#### Notes:

1. Pulse Test: Pulse Width  $\leq 300\mu s$ , Duty Cycle  $\leq 2\%$ .
2.  $R_{DS(ON)}$  calculated by TO-220 Package Type.